EFFECT OF N-TYPE TRANSITION METAL DICHALCOGENIDE MOLYBDENUM TELLURIDE (N-MoTe₂) IN BACK CONTACT INTERFACE OF CADMIUM TELLURIDE SOLAR CELLS FROM NUMERICAL ANALYSIS

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The effects of unintentionally formed n-type transition metal dichalcogenide namely molybdenum telluride (MoTe₂) in between Cadmium Telluride (CdTe) absorber layer and Mo back contact is studied from numerical modeling and analysis. The main objective is to analyze the possible effects of n-MoTe₂ formation in CdTe thin film solar cell. Energy band line-up of Mo/MoTe₂/CdTe interface is investigated in order to explain the interface properties with different parameters. Carrier concentration, bandgap energy, electron affinity and thickness of n-MoTe₂ have been varied in the numerical simulation to observe its effects on overall photovoltaic performance. The increase in the carrier concentration and bandgap energy of n-MoTe₂ deteriorates the overall performance. This could be attributed to the high value of built-in-potential (Vbi) along with band offset value at n-MoTe₂/p-CdTe interface, which causes the electrons to be drifted back towards the back contact and results in recombination. Advantageous effects are observed as the electron affinity of n-MoTe₂ is increased. This can be explained by the lower value of band offset (ΔE_C and ΔE_V) at n-MoTe₂/p-CdTe interface that interrupts the flow of carriers in overall circuit in a moderate way. Numerical results reveal that n-MoTe₂ layer thinner than 50 nm affects adversely, possibly due to the shunting.

(Received April 8, 2014; Accepted June 9, 2014)

Keywords: Thin film solar cells, CdTe, Substrate configuration, MoTe₂

1. Introduction

Cadmium Telluride (CdTe) based solar cell, as shown in Fig. 1, is one of the promising candidates due to its high efficiency and low cost potentials among the thin film groups. Up to date, the highest attained efficiency in case of CdTe solar cell is about 20.4% [1]. Besides, amongst thin film solar cells, CdTe has the largest PV industrial production with lowest cost of USD 0.75, while the module efficiency was about 11% [2, 3]. However, due to its high work function (5.79 eV), it is quite hard to find an appropriate metal as back contact. Most of the high efficiency reported until now are using some pseudo contact layers between the back contact layer and CdTe absorber layer [4-7]. Hence, molybdenum (Mo) is a prominent back contact for CdTe thin film solar cell with work function of 4.6 eV [8]. In comparison with other back contacts (for example gold, platinum), Mo is low cost as well as more available. Formation of ohmic back contact is very much important in order to reduce the series resistance for solar cells. As found from other studies related to CIGS, unintentionally formed transition metal dichalcogenide, p-
MoSe₂ in between the CIGS and Mo interface reduces the series resistance as well as enhances the overall performance for CIGS solar cells. However, for CdTe solar cells instead of p-MoSe₂, p-MoTe₂ or n-MoTe₂ may form at the interface of Mo and CdTe that may have a major impact on overall cell performance.

In this study, we demonstrate the possible effects of unintentionally formed transition metal dichalcogenide, n-MoTe₂ layer in between the CdTe absorber layer and Mo back contact from theoretical approach along with numerical modeling.

![Fig. 1: Schematic diagram of CdTe solar cell with MoTe₂ layer](image)

**2. Methodology**

**2.1 Device simulation**

In this numerical study, AMPS-1D software is used to analyze the effects of unintentionally formed MoTe₂ layer in CdTe thin film solar cell. By introducing the various material parameters into AMPS-1D software (as given in Table 1) for all sorts of possible analysis aspects, effects on the values of efficiency, Jsc, Voc and FF of are observed [9-16]. In this study, we have investigated the effects of unintentionally formed n-type MoTe₂ at the back contact as the worst case scenario. The carrier concentration and the electron affinity of n-MoTe₂ is have been changed from 1×10¹³ to 1×10¹⁷ cm⁻³ and 3.8 to 4.2 eV, while the energy bandgap and the thickness of n-MoTe₂ layer varied from 0.91 to 1.1 eV and from 10 to 100 nm, respectively, in order to observe its effect on the overall performance of the CdTe solar cells.

**Table 1. Material Properties used in Numerical Analysis**

<table>
<thead>
<tr>
<th>Property</th>
<th>SnO₂</th>
<th>Zn₂SO₄</th>
<th>CdS</th>
<th>CdTe</th>
<th>MoTe₂</th>
</tr>
</thead>
<tbody>
<tr>
<td>Thickness (µm)</td>
<td>0.07</td>
<td>0.1</td>
<td>0.08</td>
<td>2</td>
<td>0.01-0.1</td>
</tr>
<tr>
<td>εᵣ</td>
<td>9</td>
<td>9</td>
<td>9</td>
<td>9.4</td>
<td>13</td>
</tr>
<tr>
<td>μₑ (cm² V⁻¹ s⁻¹)</td>
<td>100</td>
<td>32</td>
<td>350</td>
<td>320</td>
<td>110</td>
</tr>
<tr>
<td>μₑ (cm² V⁻¹ s⁻¹)</td>
<td>25</td>
<td>3</td>
<td>50</td>
<td>40</td>
<td>426</td>
</tr>
<tr>
<td>Nₐ (cm⁻³)</td>
<td>0</td>
<td>0</td>
<td>0</td>
<td>5×10¹⁶</td>
<td>0</td>
</tr>
<tr>
<td>N₀ (cm⁻³)</td>
<td>10¹⁷</td>
<td>10¹⁷</td>
<td>10¹⁹</td>
<td>0</td>
<td>4×10¹⁹-4×10¹⁸</td>
</tr>
<tr>
<td>Eₑ (eV)</td>
<td>3.6</td>
<td>3.35</td>
<td>2.42</td>
<td>1.45</td>
<td>0.91-1.1</td>
</tr>
<tr>
<td>Nᵣ (cm⁻³)</td>
<td>2.2×10¹⁸</td>
<td>2.2×10¹⁸</td>
<td>2.2×10¹⁸</td>
<td>7.5×10¹⁷</td>
<td>3×10¹⁸</td>
</tr>
<tr>
<td>Nᵥ (cm⁻³)</td>
<td>1.8×10¹⁹</td>
<td>1.8×10¹⁹</td>
<td>1.8×10¹⁹</td>
<td>4×10¹⁸</td>
<td>4×10¹⁸</td>
</tr>
<tr>
<td>χ (eV)</td>
<td>4.5</td>
<td>4.5</td>
<td>4.5</td>
<td>4.28</td>
<td>3.8-4.2</td>
</tr>
</tbody>
</table>
2.2 Theoretical analysis

As MoTe₂ is a semiconducting material, it can be either n-type or p-type. The interface properties of Mo/MoTe₂/CdTe strongly depend on the conductivity type of MoTe₂. The Mo/MoTe₂ metal-semiconductor interface can be either an ohmic type or a rectifying type, precisely depending on the metal (Φₘ) and semiconductor work functions (Φₛ). The difference between the values of semiconductor and metal work function potentials is commonly known as Equilibrium contact potential (V₀). The equilibrium contact potential (V₀) which forms in between Mo and MoTe₂ is also assumed to be influenced by the various types of conductivity of MoTe₂ layer. This is due to the dependency of Φₛ to the doping level (N_D or N_A) as well as conductivity type (n or p) of the semiconductor material itself. In case of a metal and n-type (or p-type) semiconductor junction, diffusion of electrons (or holes) is prevented by V₀ from the semiconductor side to the metal side. From the hetero-junction formation point of view it can be said that, p-type MoTe₂ forms isotype hetero-junction while n-type MoTe₂ will forms aniso-type hetero-junction with p-CdTe absorber layer. Here, conduction band offset (ΔE_c) and valence band offset (ΔE_v) for both n-MoTe₂/CdTe and p-MoTe₂/CdTe are similar in values as long as electron affinity and energy bandgap are not dependent on the doping profile. Fig. 2 shows the possible Mo/MoTe₂/CdTe interface configurations that might take place.

3. Results and Discussion

The band profile of Mo/MoTe₂/CdTe structure as shown in Fig. 3 is analyzed in order to reveal the metal-semiconductor-semiconductor properties. The type of contacts for both Mo/n-MoTe₂ and Mo/p-MoTe₂ structures as shown in Table 2 are found to be highly effected with the variation in MoTe₂ doping level (degenerate is assumed). This is because, the Fermi level of Mo (E_Fm) lies in between the energy band structure of MoTe₂. Hence, n-MoTe₂ may forms ohmic contact or rectifying contact with Mo depending upon the doping level of MoTe₂. While the contact formation between p-MoTe₂ and Mo is always rectifying in nature. However, the equilibrium contact potential (V₀) which inhibits the diffusion of hole into metal in Mo/p-MoTe₂ structure decreases as the doping level (N_A) in being lowered. Lower doping level causes the Fermi level to be shifted upwards.

![Fig. 2: Schematic diagram of Mo/MoTe₂/CdTe interfaces](image)
Hence, due to this semiconductor work function potential and subsequently, $V_0$ decreases. In overall it can be deduced that, the interface properties p-MoTe$_2$ in CdTe solar cell is similar to the interface properties of p-MoSe$_2$ in CIGS solar cell. The contact formation of p-MoTe$_2$ with Mo in CdTe solar cell is rectifying in nature, which is exact similar to the p-MoSe$_2$ in CIGS solar cell. It should not be confound with the fact that p-MoSe$_2$ makes an ohmic contact with CIGS absorber layer, not with Mo back contact.

Undesirable effect is noticed in the photocurrent collection for CdTe solar cells with n-MoTe$_2$ layer for the doping level of $1 \times 10^{18}$ cm$^{-3}$. Fig. 4 exhibits the performance parameters of CdTe solar cells with various n-MoTe$_2$ carrier concentrations.
Variation in the carrier concentrations of n-MoTe₂ affects both of Mo/n-MoTe₂ and n-MoTe₂/p-CdTe interface properties. As mentioned earlier, while the carrier concentration of n-MoTe₂ increases, the Fermi level shifts upwards that is closer to the conduction band edge. Hence, this phenomenon causes the semiconductor work function potential to be decreased. The contact type of n-MoTe₂ with Mo highly depends upon the doping level of n-MoTe₂. For high doping level, n-MoTe₂ forms schottky contact with Mo which can be advantageous for the solar cell (possibly due to less recombination). However, increasing the doping level of n-MoTe₂ causes the built in potential ($V_{bi}$) at n-MoTe₂/p-CdTe interface to be increased, while $V_{bi}$ of the semiconductor interface diode is directly proportional to the carrier concentration at both side of the semiconductor in a p-n junction. Due to this additional built in potential, electrons that are photo generated in the vicinity of n-MoTe₂/p-CdTe interface will be drifted back to the back contact. Hence, the carriers will move in the opposite direction in which they move in conventional solar cells. However, the carriers will be hindered while moving through Mo/n-MoTe₂ interface as the contact is Schottky type. Thereby, this phenomenon tends to increase the recombination rate at the back contact diode. Besides, at the same time holes will repel to the front contact, which will result in the net photo-generated current to be decreased. Hence, this is consistent with the results from this numerical study. It was observed that, when as the carrier concentration is increased $1\times10^{16}$ to $1\times10^{18}$ cm$^{-3}$ J$sc$ drops almost 51.84 %. Besides, solar cell performance parameters like as $V_{oc}$, FF as well as efficiency decrease drastically as doping level of n-MoTe₂ increases from $10^{16}$ to $10^{17}$ cm$^{-3}$ (Fig. 4). On the other hand, as the doping level n-MoTe₂ decreases, it gradually forms ohmic contact with Mo, which can be detrimental to overall solar cell performance by increasing the recombination rate at the back contact diode. By lowering the doping level of n-MoTe₂, the built-in-potential at n-MoTe₂/p-CdTe interface also decreases. Therefore, the probability of photo-generated electrons which are drifted back to the back contact by the additional built in potential ($V_{bi}$) will be minimized. Hence, overall solar cell performance is improved. This observation implies that the unfavorable Mo/n-MoTe₂ interface property due to the increase in n-MoTe₂ carrier concentration is somehow offset by the favorable changes in n-MoTe₂/p-CdTe interface. Solar cell performance parameters like as $V_{oc}$, $I_{sc}$, FF as well as efficiency improves as doping level of n-MoTe₂ decreases. Hence, it can be concluded that doping level of n-MoTe₂ is inversely proportional to solar cell performance parameters from this numerical study.

Table 2. Mo/MoTe₂/CdTe interface properties.

<table>
<thead>
<tr>
<th>MoTe₂</th>
<th>Mo-MoTe₂ contact type (Ohmic)</th>
<th>Mo-MoTe₂ contact type (Rectifying)</th>
</tr>
</thead>
<tbody>
<tr>
<td>p-type</td>
<td>$\Phi_{Mo} &gt; \Phi_p$</td>
<td>$\Phi_{Mo} &lt; \Phi_p$</td>
</tr>
<tr>
<td>n-type</td>
<td>$\Phi_{Mo} &lt; \Phi_n$</td>
<td>$\Phi_{Mo} &gt; \Phi_p$</td>
</tr>
</tbody>
</table>
On the variations in the bandgap energy of n-MoTe$_2$, even a small increment (<0.2 eV) the CdTe solar cell conversion efficiency degrades (Fig. 5). An increase in the bandgap energy value, that is from 0.91 eV to 1.1 eV causes the conversion efficiency to be decreased. Increment in the n-MoTe$_2$ bandgap (Possibly due to downward shift of $E_v$ as well as upward shift of $E_c$) decreases the electron affinity. As a result, the value of conduction band offset ($\Delta E_c$) increases and valance band offset ($\Delta E_v$) decreases. In general, the value of $\Delta E_c$ at n-MoTe$_2$/p-CdTe junction is a lower value (< 0.1 eV), While the value of $\Delta E_v$ is quite high (> 0.6). Table 3 shows the possible values of band offset at n-MoTe$_2$/p-CdTe junction on the variation of MoTe$_2$ bandgap energy. The equations used to calculate the values of $\Delta E_c$ and $\Delta E_v$ are given below,

$$\Delta E_c = \chi_{\text{CdTe}} - \chi_{\text{MoTe}_2} \tag{1}$$

$$\Delta E_v = (\chi + E_g)_{\text{CdTe}} - (\chi + E_g)_{\text{MoTe}_2} \tag{2}$$

Here, $E_g$ is energy and $\chi$ is electron affinity bandgap in both equation (1) and (2). As the bandgap energy value of n-MoTe$_2$ is increasing (Possibly due to downward shift of $E_v$ and upward shift of $E_c$), $\Delta E_v$ is decreasing, though the value is still high (> 0.49 eV) for holes to transport towards n-MoTe$_2$. Besides, $\Delta E_c$ now becomes higher in value (> 0.19 eV) than before. Therefore, electrons which were drifted towards n-MoTe$_2$/p-CdTe interface with greater ease, now slightly impeded by larger value of $\Delta E_c$ (> 0.19 eV). While, hole transport is still impeded by larger value of $\Delta E_v$ (> 0.49 eV). As a result, overall cell performance decreases as shown in Fig. 5.
Table 3 Barrier height and band offset for Mo/n-MoTe2 and n-MoTe2/p-CdTe interface

<table>
<thead>
<tr>
<th>Metal work function ($\phi_m$) (eV)</th>
<th>Hetero-junction Type</th>
<th>Electron Affinity ($\chi$) (eV)</th>
<th>Barrier Height ($\phi_{BP}$) at Mo/n-MoTe2 Interface (eV)</th>
<th>$\Delta\chi$ at n-MoTe2/p-CdTe interface (eV)</th>
<th>$\Delta\chi$ at n-MoTe2/p-CdTe interface (eV)</th>
</tr>
</thead>
<tbody>
<tr>
<td>3.8</td>
<td></td>
<td>0.8</td>
<td>0.48</td>
<td>0.91</td>
<td></td>
</tr>
<tr>
<td>3.85</td>
<td></td>
<td>0.75</td>
<td>0.43</td>
<td>0.86</td>
<td></td>
</tr>
<tr>
<td>3.9</td>
<td></td>
<td>0.7</td>
<td>0.38</td>
<td>0.81</td>
<td></td>
</tr>
<tr>
<td>3.95</td>
<td></td>
<td>0.65</td>
<td>0.33</td>
<td>0.76</td>
<td></td>
</tr>
<tr>
<td>4.6</td>
<td>Anisotype</td>
<td>4</td>
<td>0.6</td>
<td>0.28</td>
<td>0.71</td>
</tr>
<tr>
<td>4.05</td>
<td></td>
<td>0.55</td>
<td>0.23</td>
<td>0.66</td>
<td></td>
</tr>
<tr>
<td>4.1</td>
<td></td>
<td>0.5</td>
<td>0.18</td>
<td>0.61</td>
<td></td>
</tr>
<tr>
<td>4.15</td>
<td></td>
<td>0.45</td>
<td>0.13</td>
<td>0.56</td>
<td></td>
</tr>
<tr>
<td>4.2</td>
<td></td>
<td>0.4</td>
<td>0.08</td>
<td>0.51</td>
<td></td>
</tr>
</tbody>
</table>

The overall cell performance varies at the variation of electron affinity as shown in Fig. 6. Positive effect was observed while electron affinity increases and performance deteriorates as electron affinity decreases.

![Graph](image.png)

*Fig. 6: CdTe performance parameter with different n-MoTe2 electron affinity*

It is well known that as the electron affinity decreases both the conduction band and the valance band move upward and vice versa. It is clear from the Fig. 3 that conduction band and valance band of CdTe take position below the conduction and valance band of MoTe2, respectively. Hence, as the electron affinity decreases the conduction band offset ($\Delta\chi_c$) and valance band offset ($\Delta\chi_v$) at n-MoTe2/p-CdTe junction increase. Consequently, both holes and electrons face a higher barrier height while moving to their respective direction. This barrier
compels the electrons and holes to drift back to the opposite direction in comparison to the
direction in the conventional solar cell. Additionally, the barrier height ($\phi_{bp}$) at Mo/n-MoTe$_2$
junction, which intends to prevent the flow of electron from n-MoTe$_2$ to back contact, also
increases as the electron affinity decreases. The possible values of barrier height ($\phi_{bp}$) on the
variation of electron affinity have given in Table 3. Besides, due to the decrease in electron affinity
of n-MoTe$_2$, the built in potential ($V_{bi}$) at n-MoTe$_2$/p-CdTe interface and equilibrium contact
potential ($V_0$) at Mo/n-MoTe$_2$ interface are also to be increased. Hence, the effect of the higher
value of $V_0$ which is beneficial for solar cell performance by preventing the backward flow of
electron is somehow offset by the higher value of $V_{bi}$. These factors enhance the electron
recombination mechanism at the back contact. Therefore, photocurrent loss increases which is
manifested by the decreasing $J_{sc}$ values as n-MoTe$_2$ electron affinity values decreases from 4.2 eV
to 3.8 eV. As a result, overall solar cell performance becomes worse. A decrease of 9.52% in the
electron affinity results in 74.17% decrease in conversion efficiency. On the contrary, solar cell
performance parameter parameters such as $V_{oc}$, $J_{sc}$, FF as well as efficiency improve as the electron
affinity increases. This could be due to the lower value of band offset ($\Delta E_c$ and $\Delta E_v$) as well as
lower value of $V_{bi}$ at n-MoTe$_2$/p-CdTe interface. By increasing the electron affinity, $V_0$ at Mo/n-
MoTe$_2$ interface decreases, which helps to reduce the recombination rate by preventing the flow of
electron to the back contact. However, this unfavorable effect is somehow offset by the favorable
effect of the lower value of $V_{bi}$ at n-MoTe$_2$/p-CdTe interface and consequently, solar cell
performance improves.

![Graphs showing CdTe performance parameters](image)

**Fig. 7. CdTe performance parameter with different n-MoTe$_2$ thickness.**

From the numerical study as shown in the Fig. 7 it is found that MoTe$_2$ ($E_g=0.97$ eV) layer
thinner than 50 nm is detrimental for overall CdTe solar cell performance. This is because n-
MoTe$_2$ layer with low thickness causes lower shunt resistance that is evident from the lower value
of $V_{oc}$. Hence, depend upon the numerical results from this it is very likely that, n type MoTe$_2$
layer with appreciable thickness forms in between Mo back contact and p-CdTe absorber layer.
4. Conclusion

In this study, the effects of unintentionally formed n-MoTe$_2$ layer in between CdTe absorber layer and Mo back contact is studied from numerical analysis. The results from numerical modeling show that n-MoTe$_2$ layer has some undesirable effect on the CdTe solar cell performance due to the unfavorable band line-up properties of Mo/n-MoTe$_2$ and n-MoTe$_2$/p-CdTe interfaces. Adverse effect is also observed as carrier concentration and bandgap energy value of n-MoTe$_2$ increases. This is due to the high built-in-potential ($V_{bi}$) and band offset ($\Delta E_C$ and $\Delta E_V$), which eventually cause higher recombination rate. Decreasing the electron affinity of n-MoTe$_2$ decreases the short circuit current ($J_{sc}$) values by increasing the photocurrent loss. As a result, overall cell performance deteriorates. Thinner n-MoTe$_2$ (< 50 nm) also decreases the overall conversion efficiency.

Acknowledgement

The authors would like to acknowledge and appreciate the contribution of the Ministry of Higher Education of Malaysia (MOHE) through its research grant with codes FRGS/1/2013/TK07/UKM/01/3 and ERGS/1/2012/TK07/UKM/01/4. Appreciations are also extended to the Solar Research Institute (SERI), The National University of Malaysia and the VP unit of King Saud University (KSU) of Saudi Arabia.

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